

Docket No. 201180US3  
IN RE APPLICATION OF: Kousaku MATSUNO, et al.  
SERIAL NO: 09/742,423  
FILED: December 22, 2000  
FOR: SUBSTRATE TREATMENT PROCESS AND APPARATUS


ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Transmitted herewith is an Amendment w/ Marked-Up Copy in the above-identified application.

- ☒ No additional fee is required  
☐ Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.  
☐ Additional documents filed herewith:

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	36	MINUS	41	0	x \$18 =	\$0.00
INDEPENDENT	3	MINUS	3	0	x \$84 =	\$0.00
		<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS			+ \$280 =	\$0.00
		TOTAL OF ABOVE CALCULATIONS				\$0.00
		<input type="checkbox"/> Reduction by 50% for filing by Small Entity				\$0.00
		<input type="checkbox"/> Recordation of Assignment			+ \$40 =	\$0.00
		TOTAL				\$0.00

☐ A check in the amount of \$0.00 is attached.

☒ Please charge any additional Fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

☒ If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

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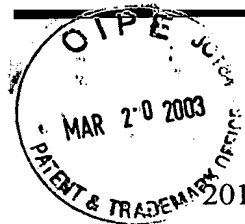
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201180US3

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF: :  
Kousaku MATSUNO, et al. : EXAMINER: KORNAKOV, M  
SERIAL NO: 09/742,423 ✓ :  
FILED: DECEMBER 22, 2000 : GROUP ART UNIT: 1746  
FOR: SUBSTRATE TREATMENT PROCESS AND APPARATUS ✓

10/a  
AS  
5/16/3

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

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SIR:

In response to the Office Action dated December 20, 2002, please amend the above-identified application as follows:

IN THE SPECIFICATION

Please replace two paragraphs at page 2, line 23, through page 4, line 17, with the following text:

As illustrative conventional techniques for such treatment of substrates, JP 10-298589 A discloses a process in which subsequent to plasma ashing of a resist, organic matter and the like on a substrate are removed using ozone water with a basic fluoride added therein. A process is proposed in JP 9-255998 A, in which ultraviolet rays are irradiated in the presence of ozone gas to remove fine organic particles which are remaining on a substrate. JP 10-41262 A discloses to use carbonated water or hydrogen water, which has been prepared by

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